Supporting Information for

Photoelectrochemistry of Colloidal Cu₂O Nanocrystal Layers:

The Role of Interfacial Chemistry

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Chemicals: copper(II) acetylacetonate ($\geq 99.9\%$), 1-octadecene (ODE, 90%), octadecylamine (ODA, $\geq 99\%$),1,2-Ethanedithiol (98%), Benzene-1,4-dithiol (99%), Benzenethiol (98%), 4-Methylbenzenethiol (98%), 4-Chlorothiophenol (97%), 4-Fluorothiophenol (98%) and 4-nitrobenzenethiol (80%), CuSO₄ (99%), lactic acid (85%), were purchased from Sigma Aldrich.



Figure S1. High resolution transmission electron (HR-TEM) cross section micrographs and electron diffraction of Cu_2O NCs film deposited on Au substrate.

Spot#	d-Spacing	Rec.	Degrees to	Degrees to	Amplitude
	(nm)	Pos.(1/nm)	Spot 1	x-axis	- implicate
1	0.3049	3.28	0	-79.97	1487
2	0.2113	4.734	22.16	-102.13	799
3	0.2261	4.423	8.46	-71.51	234
4	0.2222	4.501	173.7	106.33	248
Cu ₂ O					
5	0.303	3.3	31.2	-48.77	1462
6	0.3042	3.287	149.16	130.87	3596
7	0.2485	4.025	146.67	133.36	634
8	0.2468	4.053	57.12	-137.09	556
9	0.2111	4.737	157.54	77.57	641
10	0.2148	4.655	118.63	161.4	366
11	0.174	5.746	137.91	57.94	423
12	0.1738	5.752	42.78	-122.75	142
13	0.1523	6.566	12.96	-67.01	824
14	0.1508	6.632	167.91	112.12	695
15	0.1293	7.732	136.19	143.84	799
16	0.124	8.066	33.39	-46.58	402
Au					
17	0.2279	4.388	162.14	117.89	261
18	0.199	5.024	141.54	138.49	145
19	0.1411	7.089	124.93	155.1	83
20	0.119	8.407	118.63	161.4	86

 Table S1. Diffraction values re. Figure S1



Figure S2. (a) Contact angle values of an electrodeposited Cu₂O film and of slow evaporated layers of ODA-Cu₂O NCs, before and after ligand exchange. The ligands that were in use: Benzene-1,4-dithiol, Benzenethiol, 4-Methylbenzenethiol, 4-Chlorothiophenol, 4-Fluorothiophenol and 4-nitrobenzenethiol. (b) FTIR absorption spectra of Cu₂O NCs in KBr pellets. 24 h Ligand-exchanged NCs with Ethanedithiol (EDT, red spectrum) and Benzene-1,4-dithiol (BDT, black spectrum) are compared to the original ODA coated Cu₂O NCs ((in blue). The strong peak at 628 cm⁻¹ is assigned to the Cu(I)-O vibration and confirms the appearance of Cu₂O structure.¹⁻³ All spectra are baseline corrected and normalized according to the peak at 628 cm⁻¹. The absorption peaks at 2800-2900 cm⁻¹ and 1580 cm⁻¹ are assigned to linear alkyl chain C-H stretching and bending modes, respectively, and reduced upon ligand exchange with BDT. In parallel, a peak at around 1470 cm⁻¹ that is attributed to C-C aromatic stretching mode is clearly identified.^{4,5} Disappearance of alkyl chain vibration modes and appearance of C-C aromatic stretching modes are clear signs for successful ligand exchange from ODA to BDT. For EDT, CH stretching and bending are still present, though, at lower intensity, in agreement with the replacement of long octadecyl by shorter ethyl chains on top of the NCs.



Figure S3. Linear sweep voltammetry measurements of slow evaporated ODA-Cu₂O NCs on Au substrate (blue) and on activated Au substrate with 1,2-Ethanedithiol (red) and Benzene-1,4-dithiol (yellow). 2^{nd} backward sweeps, scan rate 10 mV/sec.



Figure S4. Linear sweep voltammograms (backward sweep #1, scan rate 10 mV/sec) of electrodeposited Cu₂O thin films (~1 μ m) on Au substrates without prior chemical activation. The electrodeposition was conducted at pH > 10. The electrochemical measurements have been conducted at dark (black) and under solar simulated AM 1.5G chopped illumination (red).



Figure S5. Linear sweep voltammetry of ODA-Cu₂O NCs, slow evaporated on Au substrates that were chemically-activated and consecutively exchanged NCs surface coating with 1,2-Ethanedithiol (red) and with Benzene-1,4-dithiol (yellow). The Au surface activation and ligand exchange were done for 60 min in chloroform 0.5 M solution. The measurements have been conducted under solar simulated AM 1.5G chopped illumination. 2^{nd} backward sweeps are presented, scan rate 10 mV/sec.



Figure S6. XRD patterns for electrodeposited Cu_2O thin film (red), compared with Cu_2O database card 01-078-2076 (black). Au database card 00-004-0784 data (blak) and ITO measured XRD pattern (green) are added, as well. The peaks of Au and ITO are marked with dashed lines.



Figure S7. X-ray photoelectron spectroscopy (XPS) measurements on deposited layers of the nanocrystals before and after ligand exchange. (a) Distinct peaks centered at 932.7 and 952.5 eV are observed and correspond to Cu $2p_{3/2}$ and Cu $2p_{1/2}$ in Cu₂O, respectively.^{6,7} Moreover, satellite Cu₂D peaks (at 942.9 and 954.2 eV) which associated with CuO and indicating Cu²⁺ having a partially filled d⁹ shell configuration in the ground state, are absent in the XPS spectra for our NCs, indicating the existence of Cu₂O phase solely and rationalized due to a full d¹⁰ shell that inhibits screening via charge transfer involving d states.³ (b) In addition, ligand exchange is confirmed by the XPS measurements, with strong sulfide peak for EDT and BDT (S2p at 162 eV), and a small, but discernible N peak for ODA (N1s at 400 eV) (inset).

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